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(54) METHOD FOR REDUCING RESISTANCE OF TRANSPARENT CONDUCTIVE FILM FORMED ON BASE MATERIAL

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a method for reducing resistance of a transparent conductive film at a low temperature using a simple process, in particular, a method for reducing the resistance of the transparent conductive film formed on a plastic base material.

SOLUTION: This method for reducing the resistance of the oxide transparent conductive film formed on the base material has a treatment process for applying ultraviolet rays to the oxide transparent conductive film formed on the base material in vacuum or reducing gas atmosphere, while keeping the conductive film at a temperature of 25-300° C.

